Application No.: 10/812,354 Docket No.071469-0308969 (FKL-020)

## IN THE UNITED STATES PATENT AND TRADEMARK OFFICE.

In re PATENT APPLICATION of: Confirmation Number: 4104

FUKIAGE, Noriaki

Application No.: 10/812.354 Group Art Unit: 1792

Filed: March 30, 2004 Examiner: LAFOND, Ronald D.

Title: Method of Improving the Wafer to Wafer Uniformity and Defectivity of a Deposited

Dielectric Film

## TRANSMITTAL AND PRELIMINARY AMENDMENT WITH RCE

Commissioner for Patents P.O. Box 1450

Alexandria, Virginia 22313-1450

June 5, 2008

Sir:

This paper is responsive to the Final Office Action dated December 05, 2007. Applicants hereby petition for a Three Month Extension of Time, payment for which is made herewith, thereby extending the due date for response to June 05, 2008. The present response includes the following:

Amendments to the Specification: None Amendments to the Claims: Pages 2-7 Amendments to the Abstract: None Amendments to the Drawings: None Remarks: Pages 8-11 Attachments: None